

67,200-477  
2000-0636

ABSTRACT

0045 A method for reducing light reflectance in photolithographic manufacturing process is disclosed including providing an inter-metal dielectric (IMD) layer including at least one via opening extending substantially perpendicular to a thickness therethrough, and, conformally forming an anti-reflectance coating (ARC) layer over (said) IMD layer such that the ARC layer is formed over sidewalls of the at least one via opening to reduce light reflectance.

TELETYPE REGISTERED TRADE NAME